

# Re-issue Radiation Characterisation of GaAs power devices in support of European Radiation Hardness

ESA-CNES FINAL PRESENTATIONS. ESTEC Noordwijk.  
6-9 March 2017

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- Radiation sensitivity of GaAs components is not so well known as compared to other technologies (Si, SiGe).
- Traditional radiation harness policy consisted in a good derating in DC bias conditions to ensure operation inside a known or expected DC safe operating area (SOA).
- However destructive single event effects (SEE) have been seen on some MESFET devices under nominal DC bias and RF signal and conditions which were compliant with standard derating requirements. Results indicate that radiation susceptibility depends on DC biasing conditions but increases with the level of RF applied to the device
- However analysis of the different manufacturer data sheets and design rule manuals shows that only DC absolute maximum rating are provided. Also all derating rules are given on DC ratings only (ECSS-Q-ST-30-11; JPL D-8545; MIL-HDBK-1547A etc.)

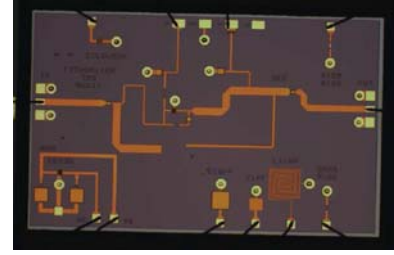
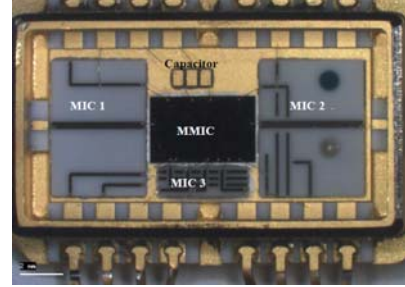
- **Are radiation tests under DC sufficient ? and if RF, what RF signals?**
- **Do we need to test other technologies than power MESFET like HEMT, pHEMT?**
- **Do we need to test per device, per lot, per function, per technology process ?**
- **What Test vehicle (TCV, DEC, MMIC) ?**
- **Have we to modify derating rules?**

➤ Under an ESA contract, TAS selected several European technologies (OMMIC D01PH pHEMT; OMMIC ED02AH pHEMT; UMS PPH25X pHEMT; UMS HP07 MESFET) and non-European ones (MITSUBISHI High Power MESFET; Sumitomo "7" Series MESFET, Sumitomo Low Noise pHEMT) to test under DC and DC+RF signals trying to achieve worst case conditions.

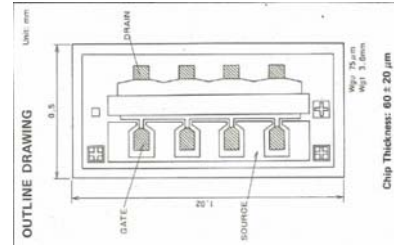
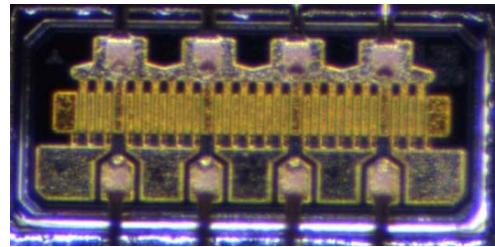
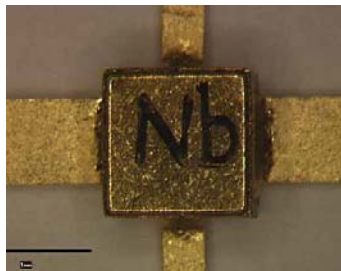
Process (FOUNDRY)	ED02AH (OMMIC)	High Power GaAs MGFC (MITSUBISHI)	High Power GaAs "7" Series FL707 (SUMITOMO)	pHEMT (SUMITOMO)	HP07 (UMS)	D01PH (OMMIC)	PPH25X (UMS)
Active device	pHEMT	MESFET	MESFET	pHEMT	MESFET	pHEMT	pHEMT
Type	Low Noise	Power	Power	Low Noise	Power	Power	Power
Power density		300 mW/mm	280 mW/mm	280 mW/mm	500 mW/mm	600 mW/mm	900 mW/mm
Gate length Emitter width	0.18-0.15 $\mu$ m	0.6 $\mu$ m	0.6 $\mu$ m	0.25 $\mu$ m	0.7 $\mu$ m	0.13 $\mu$ m	0.25 $\mu$ m
I <sub>DS</sub> (gm max) or I <sub>c</sub> HBT		40 mA/mm	170 mA/mm	140 mA/mm	300 mA/mm	400 mA/mm	170 mA/mm
I <sub>dss</sub>		160 mA/mm	170 mA/mm	140 mA/mm		360 mA/mm	450 mA/mm
BV <sub>DS</sub> / BV <sub>CE</sub>	5 V	12,5 V	25 V	4 V	> 14 V	> 9V	> 18V
Cut off freq.	63-73 GHz		15 GHz	31 GHz	15 GHz	100 GHz	45 GHz
V pinch	+0.2 / -0.9 V	-3 V	-2,3 V	-1,0 V	-4 V	-0.9 V	-0.9 V
Gm max / $\beta$		42 mS/mm	70 mS/mm	210 mS/mm	100 mS/mm	700 mS/mm	400 mS/mm
Noise / Gain	<0.5 dB @12 GHz	9dB @ 3,7-4,2 GHz	10 dB @ 3,7-4,2 GHz	1.2 dB @12 GHz	9.5dB @6GHz	15 dB @30GHz	



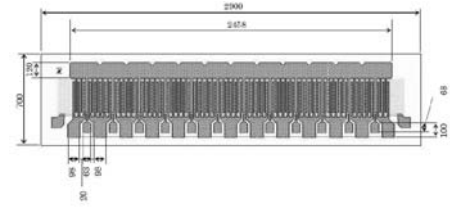
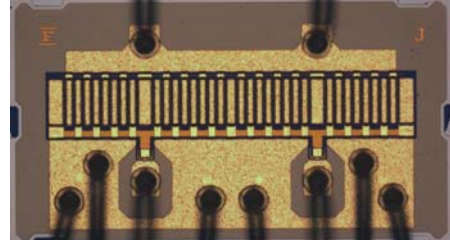
**OMMIC ED02AH**  
**TCV: FTCVOM112A**  
**(with DEC amplifier)**



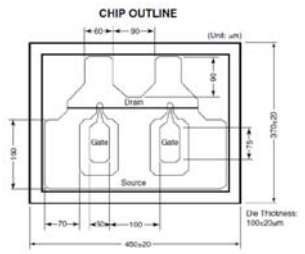
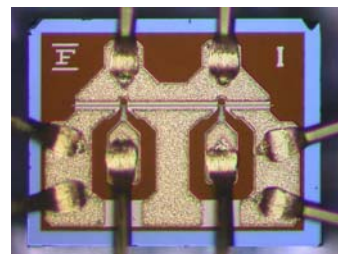
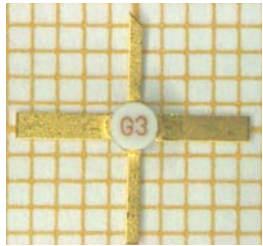
**MITSUBISHI**  
**HIGH POWER GaAs**  
**MGF2430S**



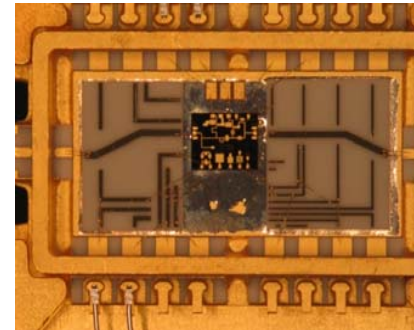
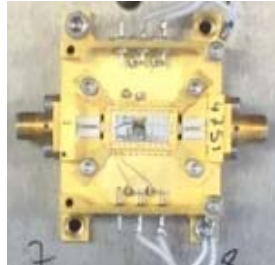
**SUMITOMO**  
**HIGH POWER GaAs**  
**FLL120MK**



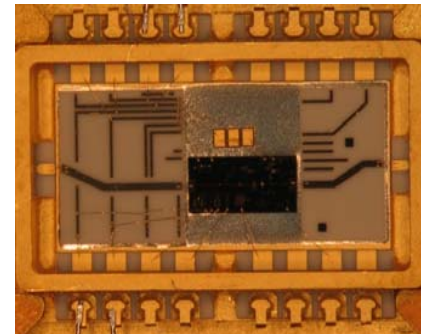
**SUMITOMO**  
**pHEMT FHX35LR**



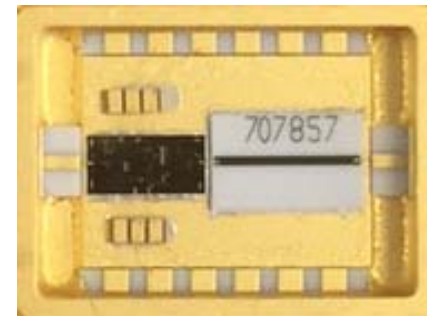
**UMS PPH25X**  
**TCV: FTCVUM102A**  
**(with DEC amplifier)**

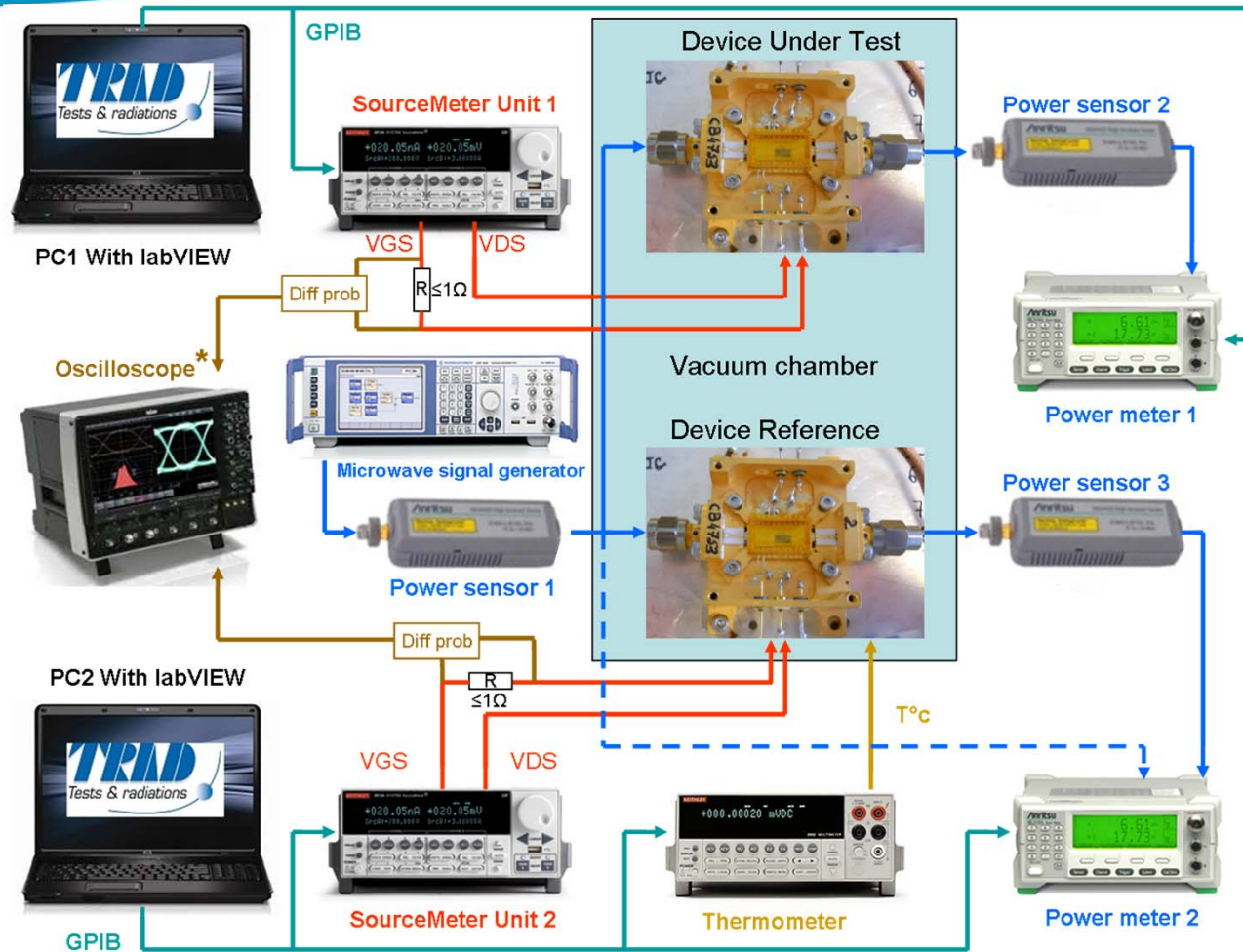


**OMMIC D01PH**  
**TCV: FTCVOM105A**  
**(with DEC amplifier)**



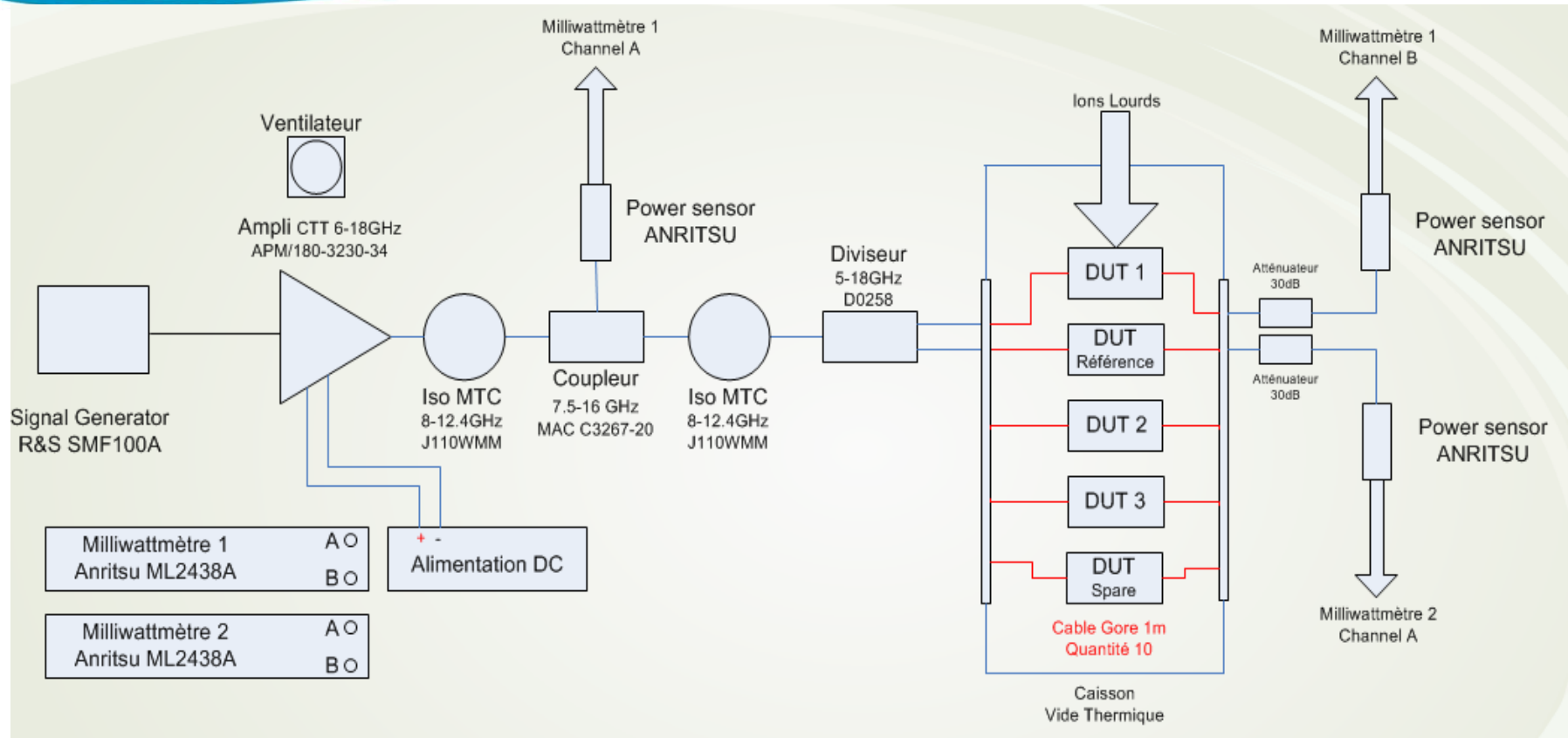
**UMS HP07**  
**TCV**  
**(with DEC amplifier)**





**Test bench overview**

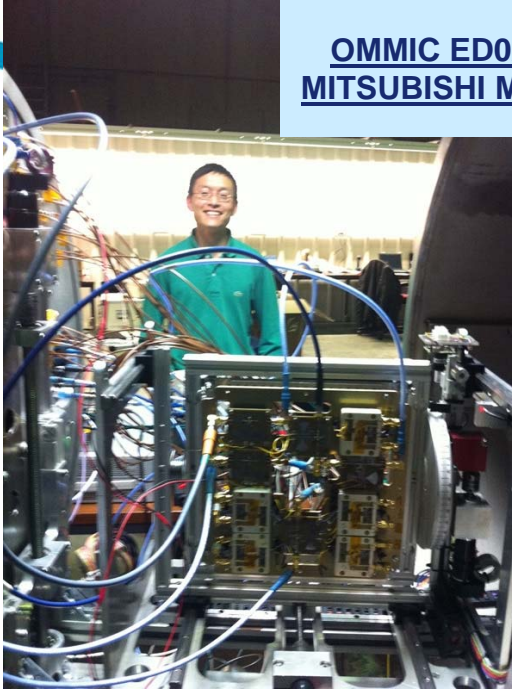




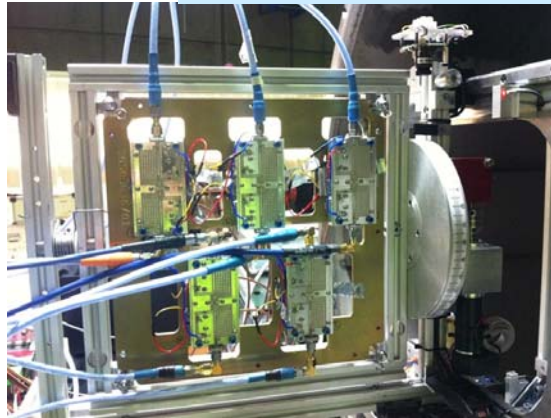
## Test bench used in UCL (Belgium)

# IRRADIATION CAMPAIGN

OMMIC ED02AH & MITSUBISHI MGF2430



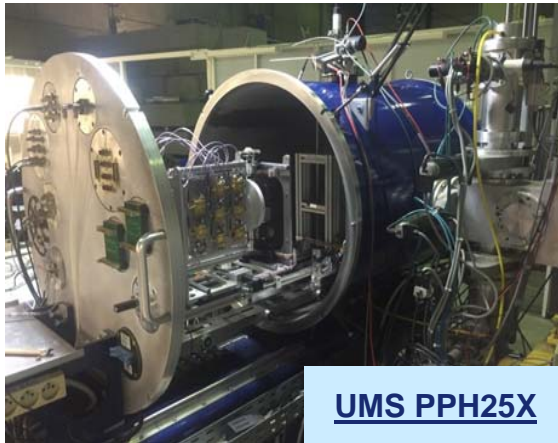
SUMITOMO pHEMT FHX35LR



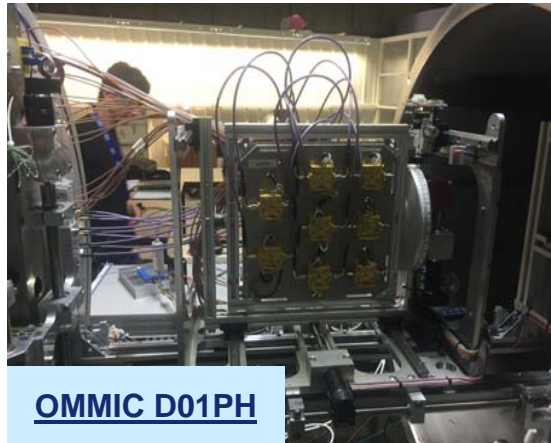
SUMITOMO FLL120MK



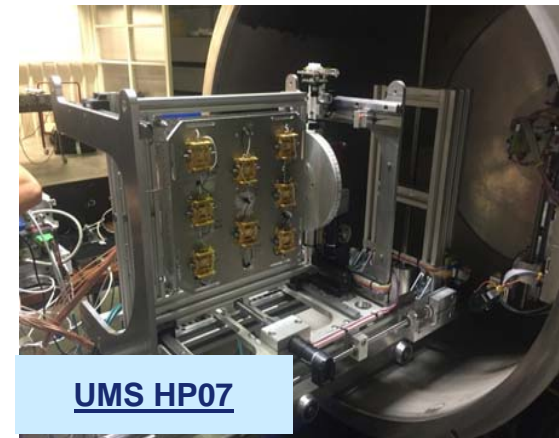
UMS PPH25X



OMMIC D01PH



UMS HP07





- Performed at the Heavy Ions Cyclotron Facility (HIF) at University of Louvain la Neuve in Belgium, on week 1547 (November 17<sup>th</sup> to 20<sup>th</sup>).
  - Ion  $^{124}\text{Xe}^{+35}$ , 995MeV, the Highest LET value available in cocktail-2: 62.5 MeV/cm<sup>2</sup>/mg in Si (effective LET in GaAs of 44.3 MeV/cm<sup>2</sup>/mg).
  - Penetration range up to 73.1 $\mu\text{m}$  in Si; 49 $\mu\text{m}$  in GaAs. Enough for a "sensitive" thickness estimated to be <20 $\mu\text{m}$  (including passivation around 1000Å SiN, contact metal around 5000Å Al, and GaAs uniform doped channel of typical <2000Å).
  - Fluence starting from  $10^6$  to  $10^7$  ions/cm<sup>2</sup> (under orthogonal impact (no tilt)).
  - 7 to 12 runs per device. 7 to 10 minutes irradiation per run
- 
- Sample size. On the same board: 3 DUT for irradiation + 1 REF biased inside the chamber + 1 attrition biased inside the chamber. Also 1 attrition outside the board (chamber).
  - Electrical Measurements before and after irradiation:
    - OUTPUT CHARACTERISTIC :  $I_{ds}$  vs ( $V_{ds}$ ,  $V_{gs}$ )
    - SCHOTTKY CHARACTERISTIC :  $I_{gs}$  vs  $V_{gs}$
    - Continuous Monitoring during irradiation:
      - $P_{in}$  (dBm) &  $P_{out}$  (dBm)
      - $I_d$  (A);  $I_g$  (A)
      - Temperature

**MITSUBISHI MGF2430S**

**Biasing**

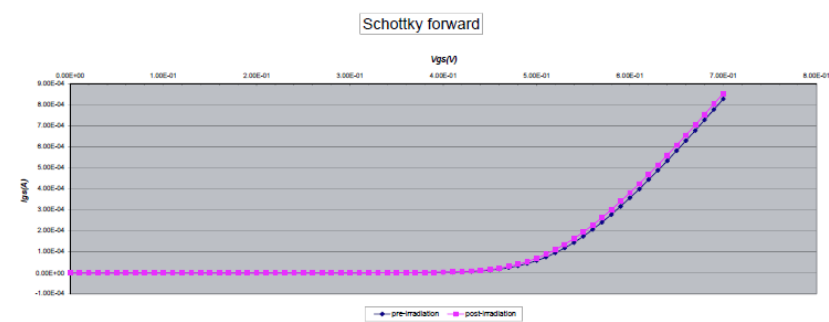
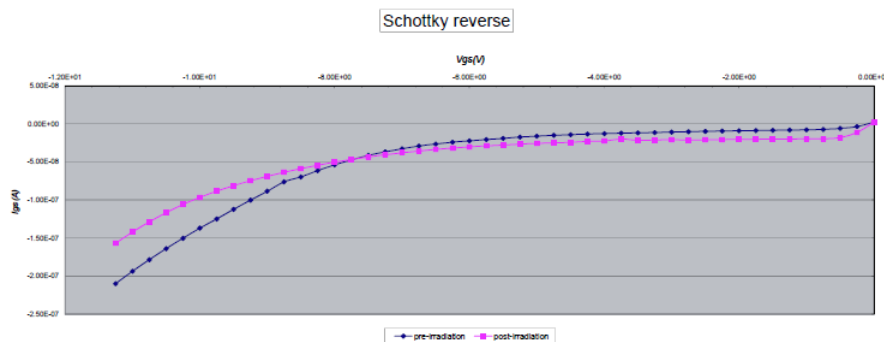
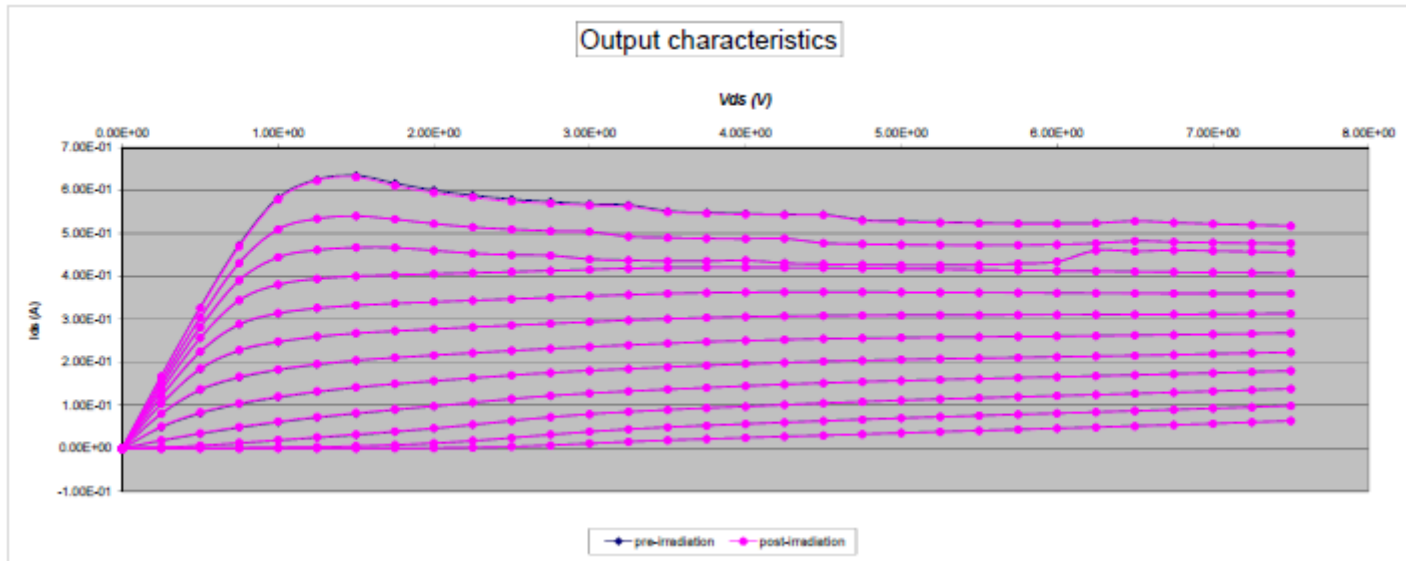
- Condition 1.1 (DC):  $V_{gs}=-4.5V$ ,  $V_{ds}$  7.5V.
- Condition 1.2 (DC):  $V_{gs}=-2.25V$ ,  $V_{ds}$  7.5V.
- Condition 2 (DC+RF):  $V_{gs}= -1.03V$ ,  $I_d=300mA$ ,  $V_{ds}=7.5V$ , CW Input power=25dBm, input frequency=1.85GHz. Compression Level = 6dB

**Measurements**

- $I_{ds}$  vs  $V_{gs}$  &  $V_{ds}$
- $I_{gs}$  vs  $V_{gs}$
- Monitoring during irradiation:  $P_{in}$  &  $P_{out}$ ;  $I_d$ ;  $I_g$ ; Temperature

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN2	Step 1.1 & 1.2	Step 2	PASS
SN3	Step 1.1	Step 2	PASS
SN4	Step 1.1	Step 2	PASS

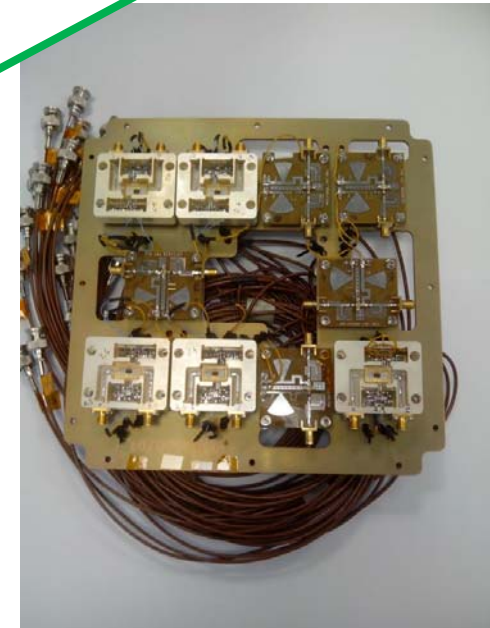
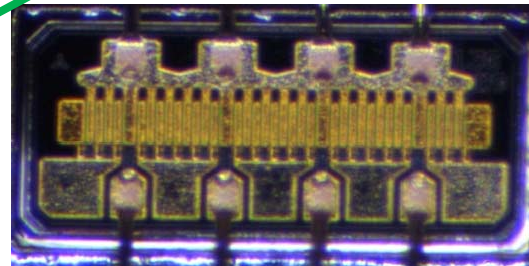




Slight difference between before and after irradiation attributed to temperature (increased during irradiation due to bad dissipation in vacuum) or test set-up

# MITSUBISHI HP MGF2430S

not sensitive to heavy  
ions up to LET of 62.5  
(MeV.cm<sup>2</sup>/mg)



**SUMITOMO FHX35LR**



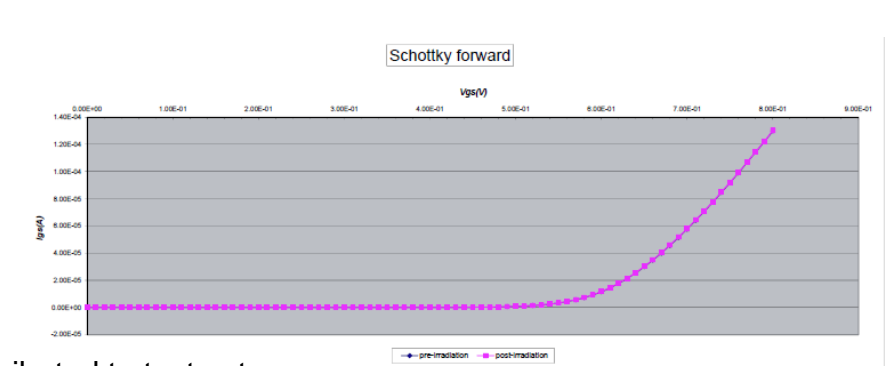
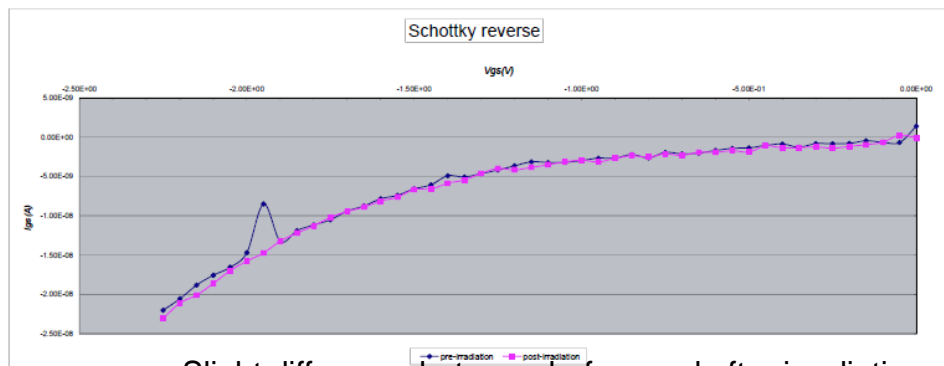
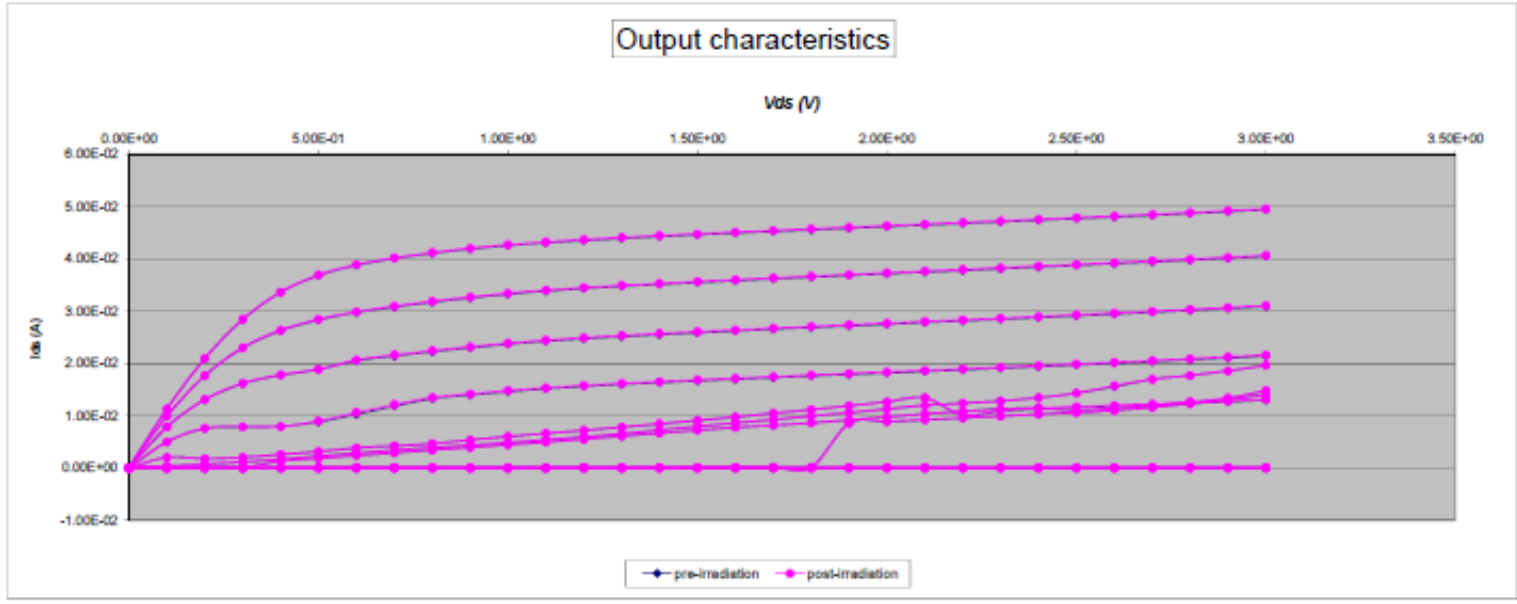
**Biasing**

- Condition 1.1 (DC): Vgs=-2V, Vds 3V.
- Condition 1.2 (DC): Vgs=-1V, Vds 3V.
- Condition 2 (DC+RF): Vgs=-0.3, Id=22mA, Vds=3V, CW Input power=1dBm, input frequency=1.85GHz. Compression Level = 6dB

**Measurements**

- Ids vs Vgs & Vds
- Igs vs Vgs
- Monitoring during irradiation: Pin & Pout; Id; Ig; Temperature

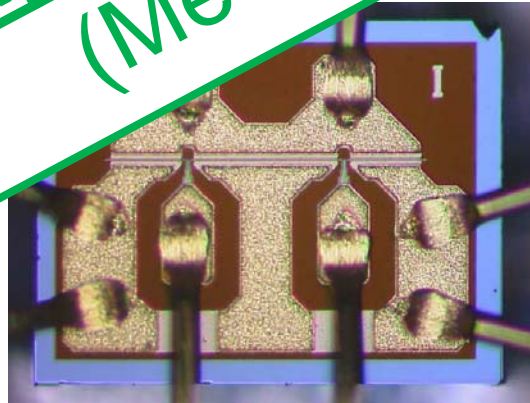
Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN2	Step 1.1 & 1.2	Step 2	PASS
SN3	Step 1.1	Step 2	PASS
SN4	Step 1.1	Step 2 Step 2 with Oscilloscope	PASS



Slight difference between before and after irradiation attributed to test set-up

# SUMITOMO FHX35LR pHEMT

not sensitive to heavy ions  
up to LET of 62.5  
(MeV.cm<sup>2</sup>/mg)





SUMITOMO FLL120MK

**Biasing**

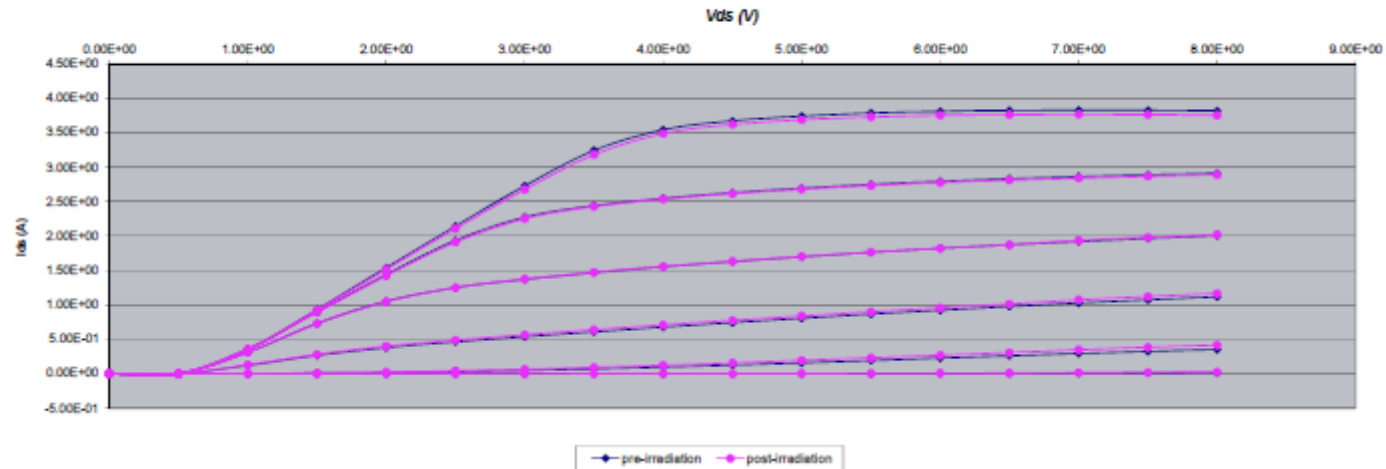
- Condition 1.1 (DC):  $V_{gs}=-3.5V$ ,  $V_{ds} 11.25V$
- Condition 1.2 (DC):  $V_{gs}=-1.75V$ ,  $V_{ds} 11.25V$
- Condition 2 (DC+RF):  $V_{gs}=-1.25V$ ,  $I_{ds}=2.2A$ ,  $V_{ds}=9V$ , CW Input power=11.7dBm, input frequency=2.3GHz

**Measurements**

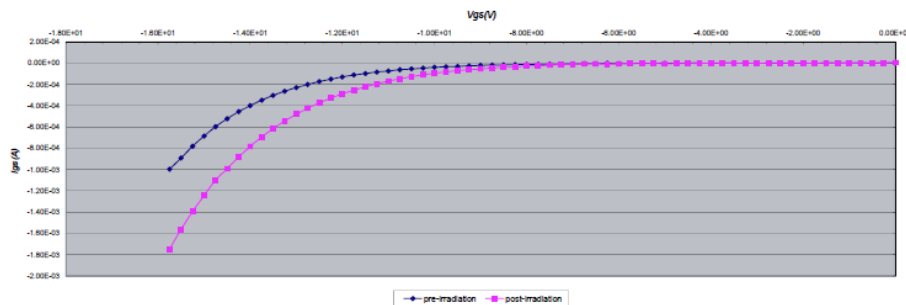
- $I_{ds}$  vs  $V_{gs}$  &  $V_{ds}$
- $I_{gs}$  vs  $V_{gs}$
- Monitoring during irradiation: Pin & Pout; Id; Ig; Temperature

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN2	Step 1.1 & 1.2	Step 2	PASS
SN3	Step 1.1	Step 2	PASS
SN4	Step 1.1	Step 2 Step 2 with Scope	PASS

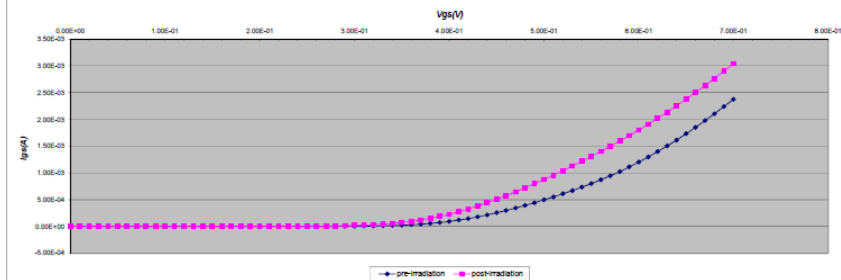
Output characteristics



Schottky reverse



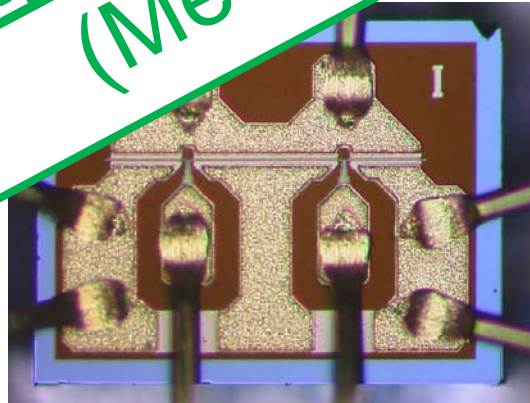
Schottky forward



Slight difference between before and after irradiation attributed to temperature (increased during irradiation due to bad dissipation in vacuum) or test set-up

# SUMITOMO HP FLL120MK

**not sensitive to heavy ions  
up to LET of 62.5  
(MeV.cm<sup>2</sup>/mg)**





**OMMIC ED02AH TCV**

**Biasing**

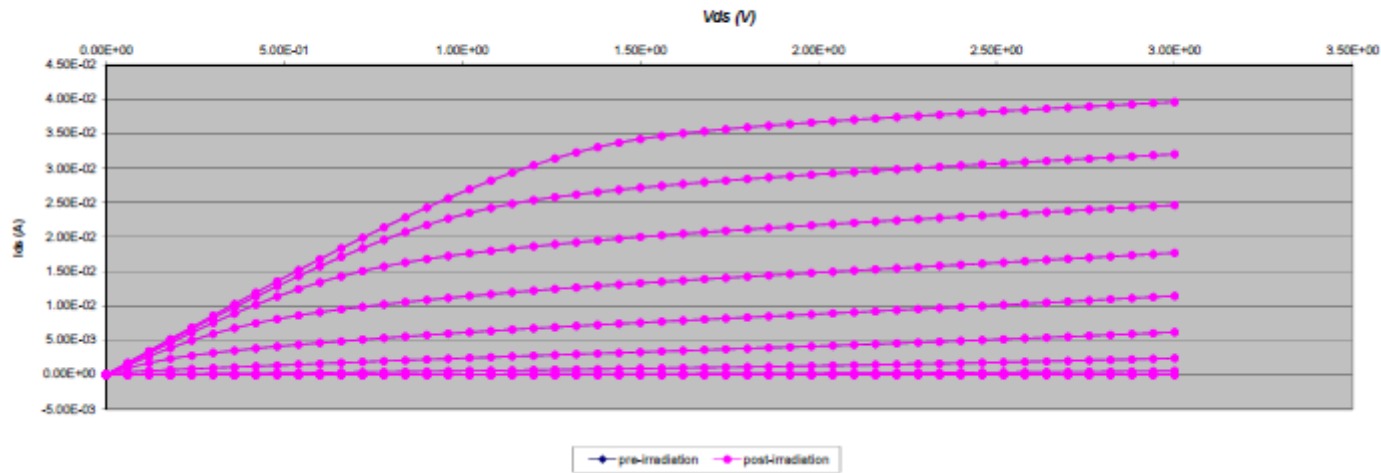
- Condition 1.1 (DC):  $V_{gs}=-3.75V$ ,  $V_{ds}$  3V
- Condition 1.2 (DC):  $V_{gs}=-1.875V$ ,  $V_{ds}$  3V
- Condition 2 (DC+RF):  $V_{gs}=-0.22V$ ,  $I_{ds}=22mA$ ,  $V_{ds}=3V$ , CW Input power=2.8dBm, input frequency=12.6GHz
- Condition 2.1: as 2 with multicarrier and CW input power = -4dBm. Multicarrier: PM modulation with subcarrier 6KHz and 1.5Rad index

**Measurements**

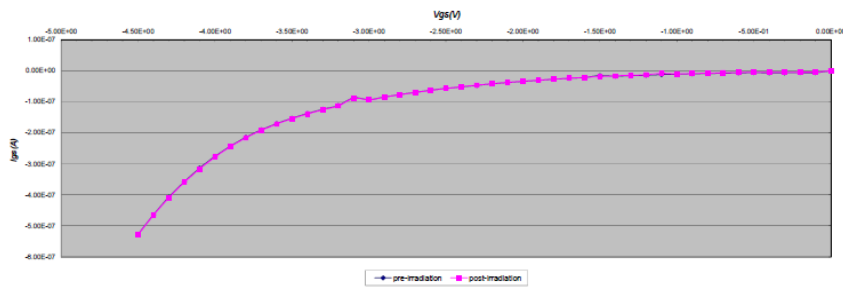
- $I_{ds}$  vs  $V_{gs}$  &  $V_{ds}$
- $I_{gs}$  vs  $V_{gs}$

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN2	TCV Step 1.1 & 1.2	DEC Step 2 & 2.1	PASS
SN3	TCV Step 1.1	DEC Step 2 & 2.1	PASS
SN4	TCV Step 1.1	DEC Step 2 & 2.1	PASS

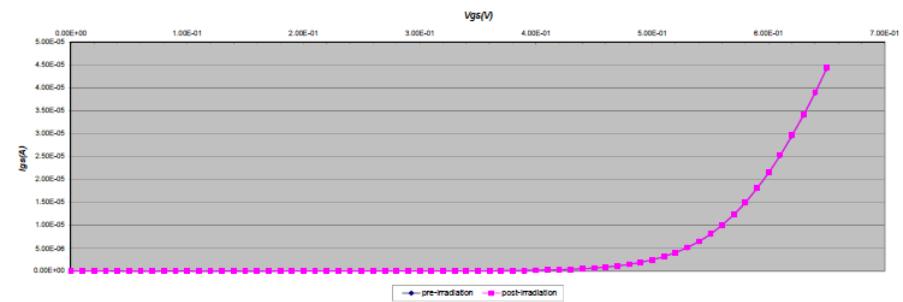
Output characteristics



Schottky reverse

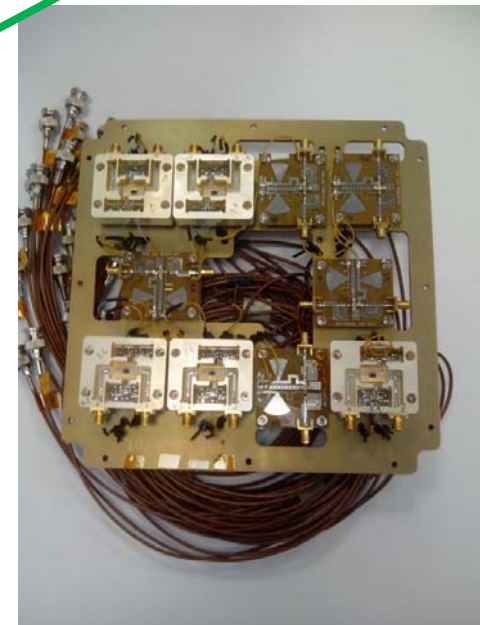
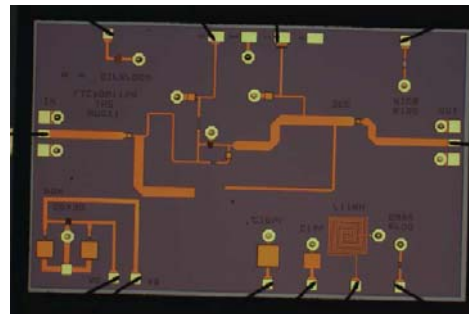


Schottky forward



# OMMIC ED02AH

not sensitive to heavy ions  
up to LET of 62.5  
(MeV.cm<sup>2</sup>/mg)

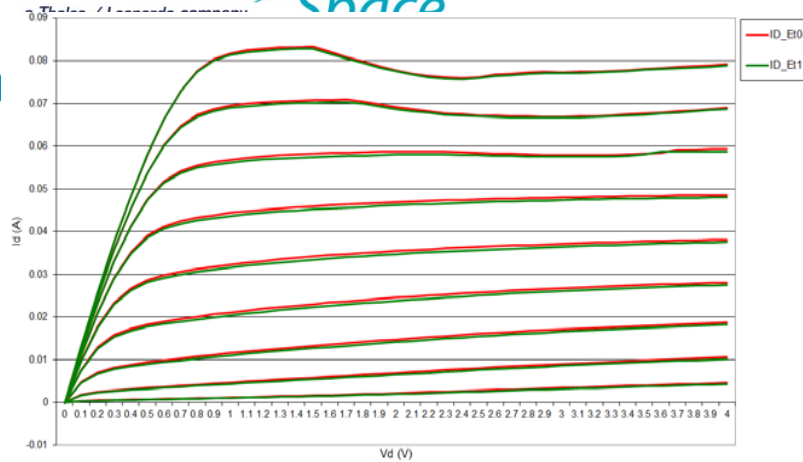




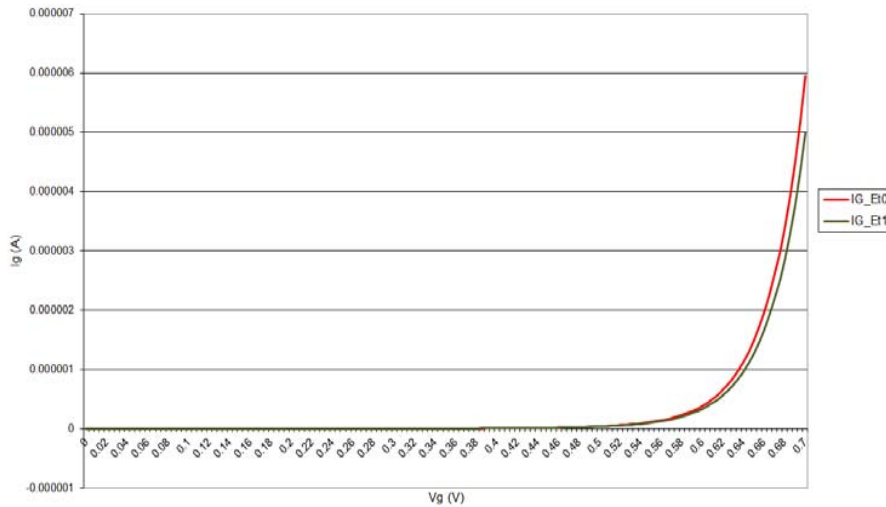
# UMS PPH25X

<b>ELECTRICAL TEST CONDITIONS 1</b>	<p><b>BVGD Sequences: On TCV devices</b></p> <p><b><u>Step 1-1 : TCV VDS nominal, VGD (DC) = VGD (RF) peak = -17 V (Based by retro simulation for 6dB GC) <u>Vds=14V, Vgs=-3V</u></u></b></p>
<b>ELECTRICAL TEST CONDITIONS 2</b>	<p><b>RF Step Stress Sequences: on DEC devices</b></p> <p><b>For DEC VDS=7 Volts, Ids= 27 mA</b></p> <p><b><u>Step 2-1 : 4 dB gain comp. <u>Pin=18,2 dBm</u></u></b></p> <p><b><u>Step 2-2 : 6 dB gain comp. <u>Pin=20,4 dBm</u></u></b></p>

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN3	Step 1.1	Step 2.2	PASS
SN4	Step 1.1	Step 2.2	PASS
SN5	Step 1.1	Step 2.2	PASS



**Output characteristic typical – SN3**



**Forward Shottky characteristic typical – SN3**

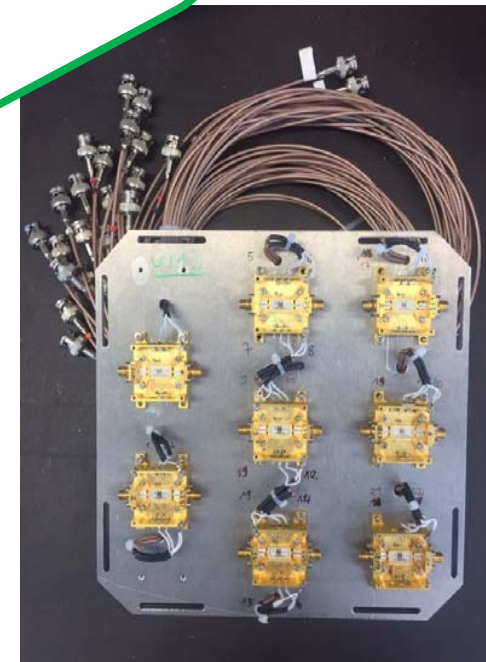
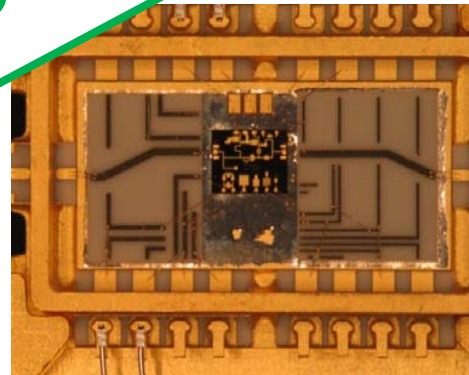
**Reverse Shottky characteristic SN1 – Control Sample**  
**Same electrical conditions without Heavy Ions**



**Reverse Shottky characteristic typical – SN3**

# UMS PPH25X

**not sensitive to heavy  
ions up to LET of 62.5  
(MeV/cm<sup>2</sup>/mg)**



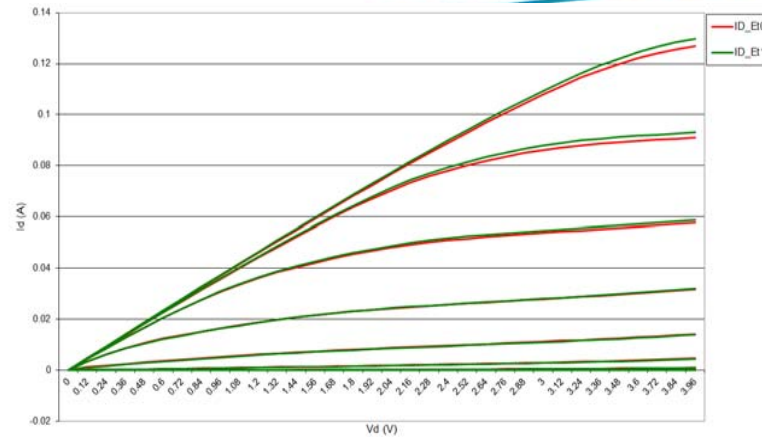


**OMMIC D01PH**

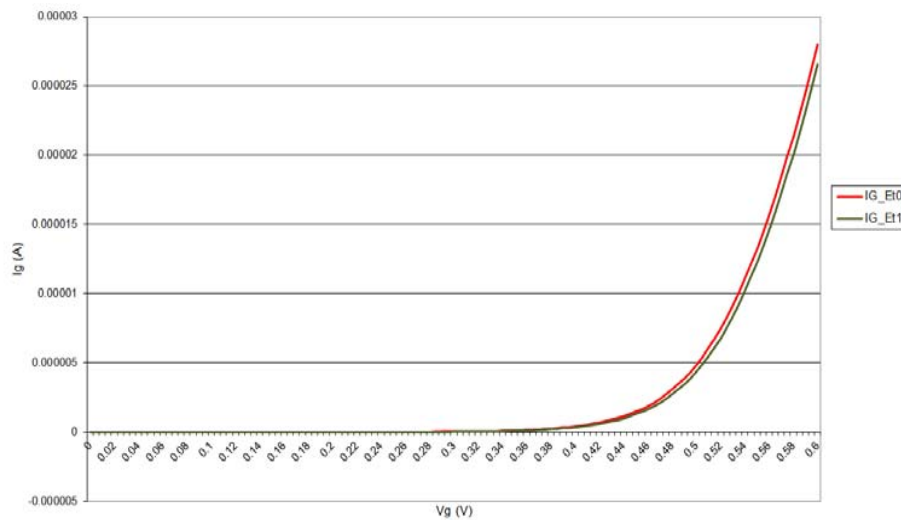
<p><b>ELECTRICAL TEST CONDITIONS 1</b></p>	<p><b>BVGD Sequences: On TCV devices</b></p> <p>Step 1-1 : TCV VDS nominal, VGD (DC) = VGD (RF) peak = -6.5 V (Based by retro simulation for 6dB GC) <u>Vds=4V, Vgs=-2.5V</u></p>
<p><b>ELECTRICAL TEST CONDITIONS 2</b></p>	<p><b>RF Step Stress Sequences: on DEC devices</b></p> <p>For DEC Vds=4 V, Ids=58 mA Step 2-1 : 4 dB gain comp. <u>Pin=15dBm</u> Step 2-2 : 6 dB gain comp. <u>Pin=17,25dBm</u></p>

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN3	Step 1.1	Step 2.2	PASS
SN4	Step 1.1	Step 2.2	PASS
SN5	Step 1.1	Step 2.2	PASS

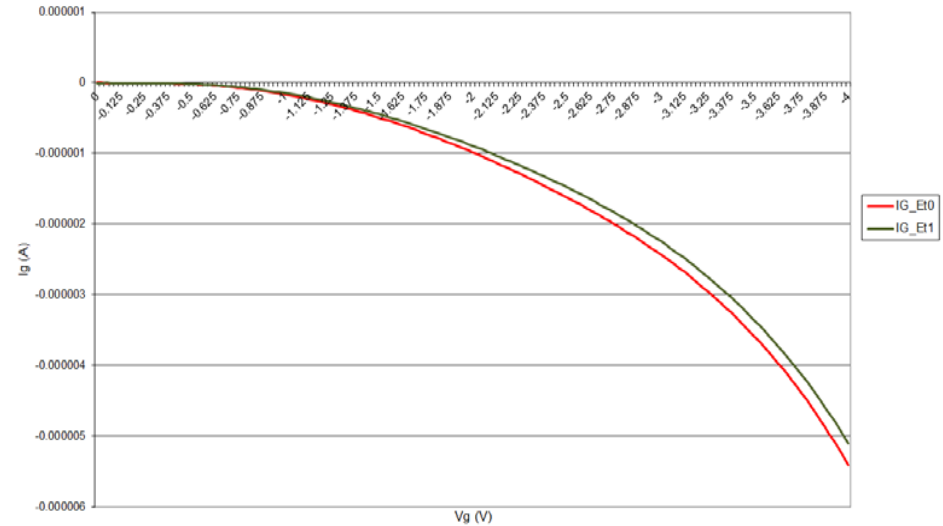
# OMMIC D01PH. STATIC CHARACTERISTICS



Output characteristic typical – SN3



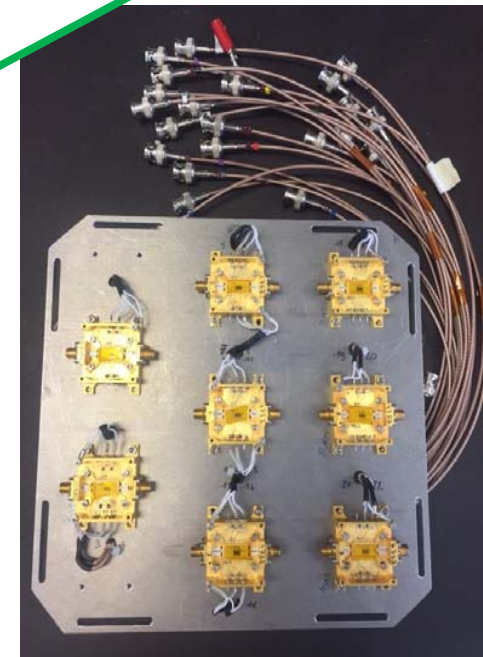
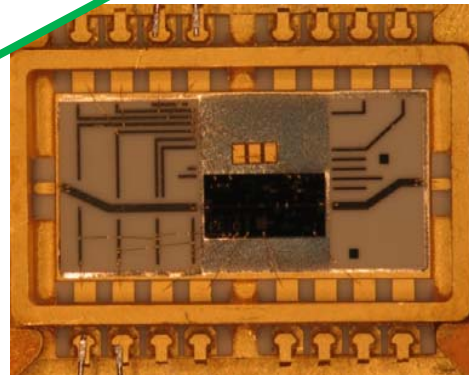
Forward Shottky characteristic typical – SN3



Reverse Shottky characteristic typical – SN3

# OMMIC D01PH

**not sensitive to heavy  
ions up to LET of 62.5  
(MeV.cm<sup>2</sup>/mg)**



# UMS HP07



<p><b>ELECTRICAL TEST CONDITIONS 1</b></p>	<p><b>BVGD Sequences: On TCV devices</b></p> <p><u>Step 1-1 : 100% ROR : <math>V_{ds}=9V, V_{gs}=-9V</math></u>  <u>Step 1-2 : 75% AMR : <math>V_{ds}=7.5V, V_{gs}=-7.5V</math></u>  <u>Step 1-3 : 100% AMR : <math>V_{ds}=10V, V_{gs}=-10V</math></u></p>
<p><b>ELECTRICAL TEST CONDITIONS 2</b></p>	<p><b>RF Step Stress Sequences: on DEC devices</b></p> <p>For DEC <math>V_{DS}=7</math> Volts, <math>I_{ds}= 270</math> mA</p> <p><u>Step 2-1 : 4 dB gain comp. <math>P_{in}=10</math> dBm</u>  <u>Step 2-2 : 6 dB gain comp. <math>P_{in}=13</math> dBm</u></p>

**A sensitivity have been observed on HP07 process during californium test (LET 40) in TRAD building.**

**(Note that sensitivity already seen in late 90's during heavy ions testing performed by TASF/CNES at  $V_{gd}<v_{gdmax}$ )**

**→ We have decided to begin the heavy ions campaign with a different LET in order to define a threshold :**

- LET 10 : ARGON
- LET 20 : NICKEL
- LET 32 : KRYPTON

<p><b>ELECTRICAL TEST CONDITIONS 1</b></p>	<p><b>BVGD Sequences: On TCV devices</b></p> <p><u>Step 1-1 : 100% ROR : Vds=9V, Vgs=-9V</u>  <u>Step 1-2 : 75% AMR : Vds=7.5V, Vgs=-7.5V</u>  <u>Step 1-3 : 100% AMR : Vds=10V, Vgs=-10V</u></p>
<p><b>ELECTRICAL TEST CONDITIONS 2</b></p>	<p><b>RF Step Stress Sequences: on DEC devices</b></p> <p>For DEC VDS=7 Volts, Ids= 270 mA</p> <p><u>Step 2-1 : 4 dB gain comp. Pin=10 dBm</u>  <u>Step 2-2 : 6 dB gain comp. Pin=13 dBm</u></p>

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN2	Step 1.1 Step 1.2 Step 1.3	Step 2.1 Step 2.2	PASS
SN4	Step 1.3	Step 2.2	PASS
SN5	Step 1.3	Step 2.2	PASS

<p><b>ELECTRICAL TEST CONDITIONS 1</b></p>	<p><b>BVGD Sequences: On TCV devices</b>  <u>Step 1-1 : 100% ROR : Vds=9V, Vgs=-9V</u>  <u>Step 1-2 : 75% AMR : Vds=7.5V, Vgs=-7.5V</u>  <u>Step 1-3 : 100% AMR : Vds=10V, Vgs=-10V</u></p>
<p><b>ELECTRICAL TEST CONDITIONS 2</b></p>	<p><b>RF Step Stress Sequences: on DEC devices</b>  For DEC VDS=7 Volts, Ids= 270 mA  <u>Step 2-1 : 4 dB gain comp. Pin=10 dBm</u>  <u>Step 2-2 : 6 dB gain comp. Pin=13 dBm</u></p>

**sensitive to heavy ions LET 20 in RF SS**

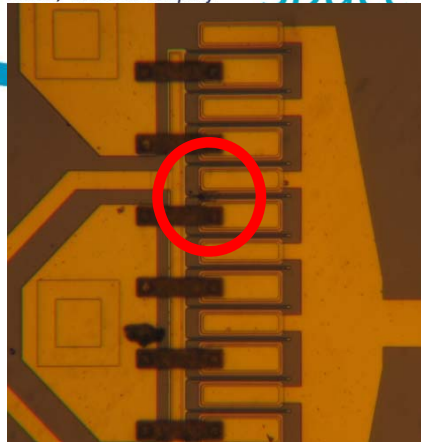
Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN5	Step 1.3	Step 2.2	PASS
SN4	Step 1.3	Step 2.2	FAIL
SN2	Step 1.3	Step 2.1	FAIL

<p><b>ELECTRICAL TEST CONDITIONS 1</b></p>	<p><b>BVGD Sequences: On TCV devices</b></p> <p><u>Step 1-1 : 100% ROR : Vds=9V, Vgs=-9V</u>  <u>Step 1-2 : 75% AMR : Vds=7.5V, Vgs=-7.5V</u>  <u>Step 1-3 : 100% AMR : Vds=10V, Vgs=-10V</u></p>
<p><b>ELECTRICAL TEST CONDITIONS 2</b></p>	<p><b>RF Step Stress Sequences: on DEC devi</b></p> <p>For DEC VDS=7 Volts, Ids= 27 mA</p> <p><u>Step 2-1 : 4 dB gain comp. Pin=10 dBm</u>  <u>Step 2-2 : 6 dB gain comp. Pin=13 dBm</u></p>

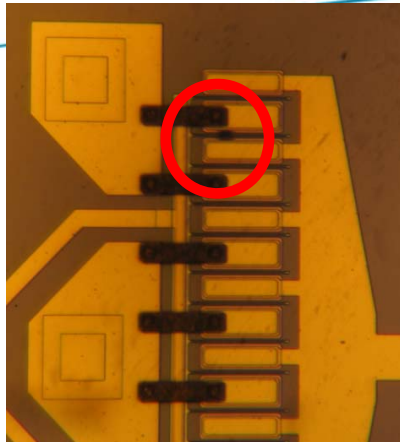
**sensitive to heavy ions LET 32 in BVGD**

Sample	BVGD Sequence	RF Step Stress Sequence	Compliance
SN1	Reference	Reference	PASS
SN6	Step 1.3		PASS
SN7	Step 1.3		FAIL
SN8	Step 1.2		FAIL
SN5		Step 2.1 with scop	FAIL

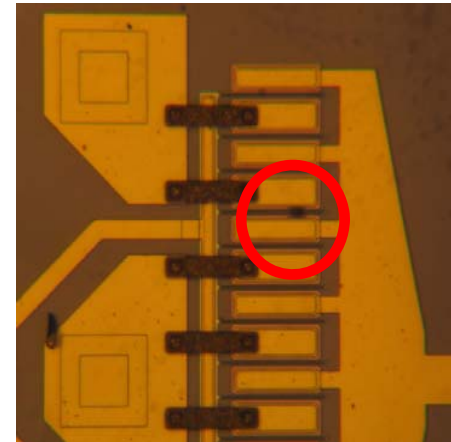
UMS HP07. SENSITIVE TO HEAVY IONS



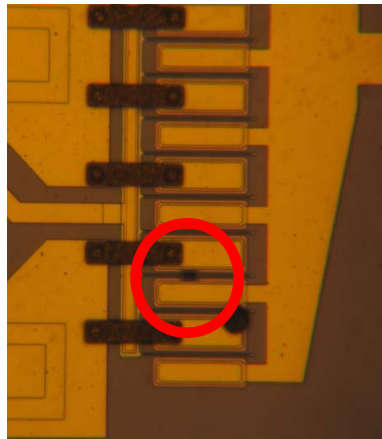
SN10 – Step 2.2 - Californium



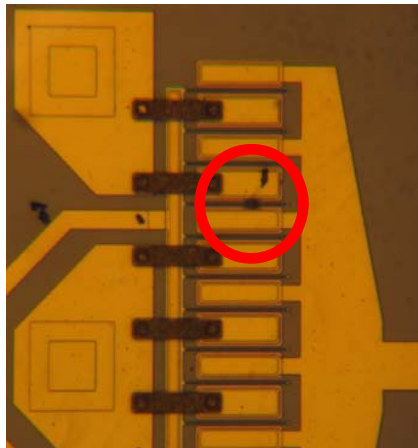
SN6 – Step 2.2 - Californium



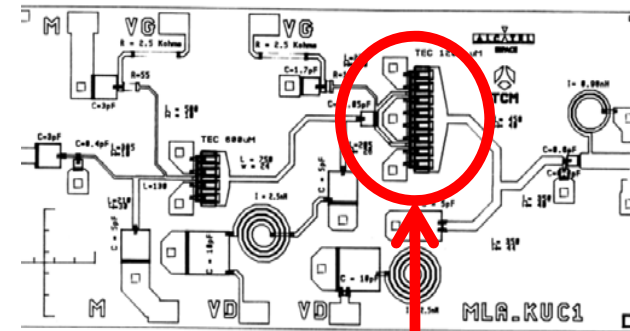
SN3 – Step 2.2 - Californium



SN2 - Step 2.1 (LET20)



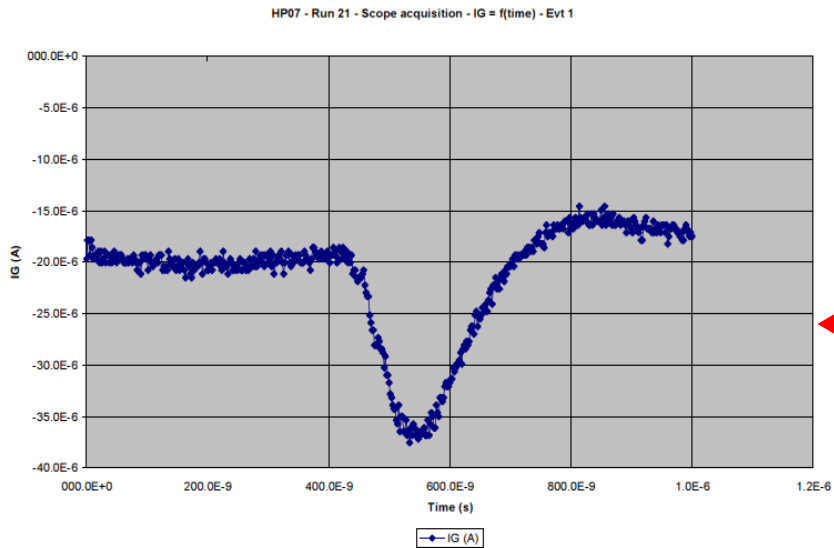
SN4 - Step 2.2 (LET20)



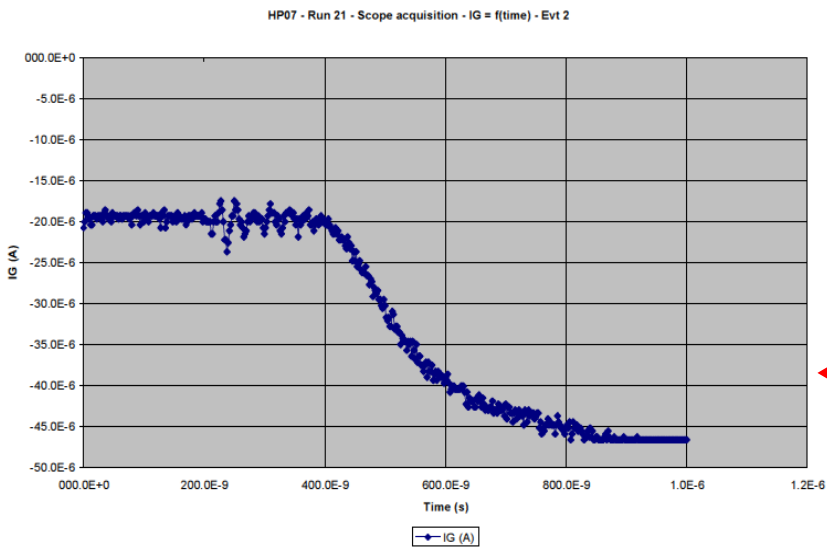
Stage 2



# UMS HP07. EVENTS OBSERVED WITH SCOPE ACQUISITION



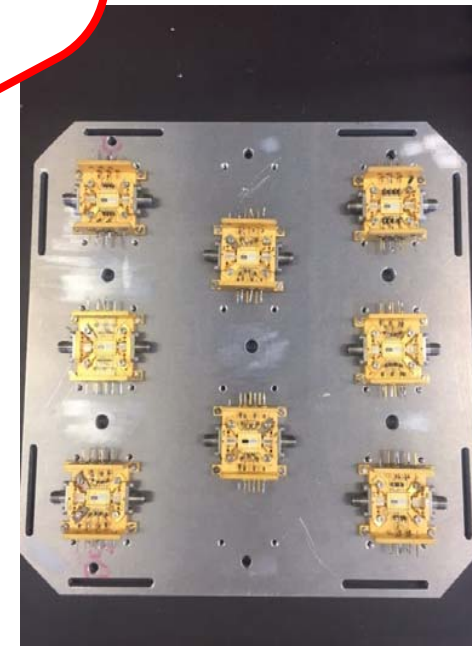
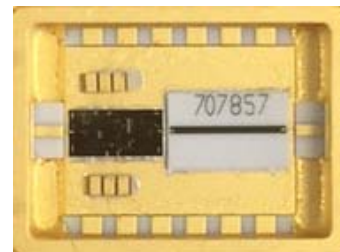
← Event observed before the failure.



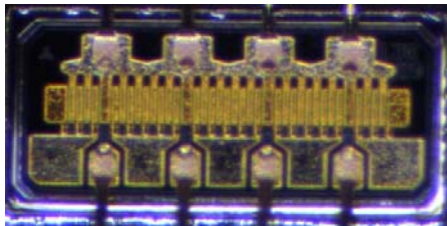
← Event observed during the failure.

# UMS HP07

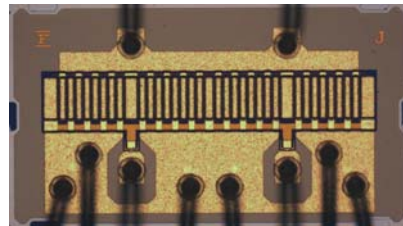
Sensitive to heavy ions :  
BVGD : Maximum LET 20  
RF SS : Maximum LET 10



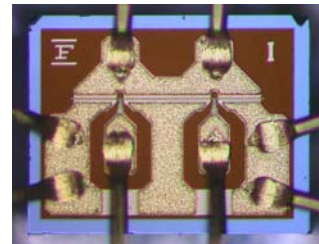
MITSUBISHI  
HP MGF2430S



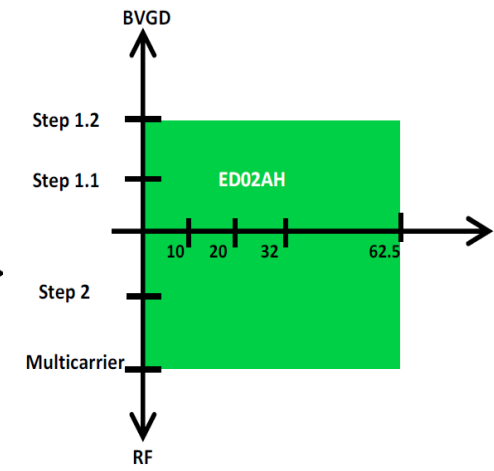
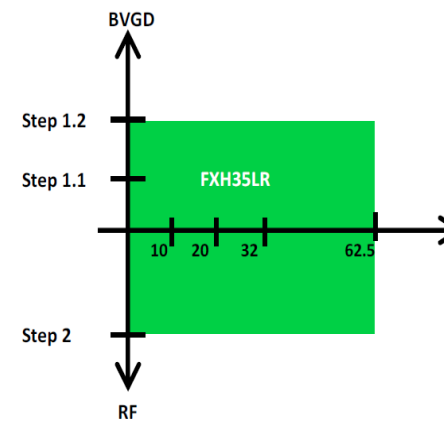
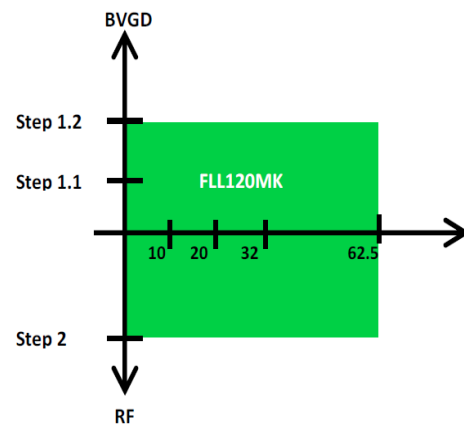
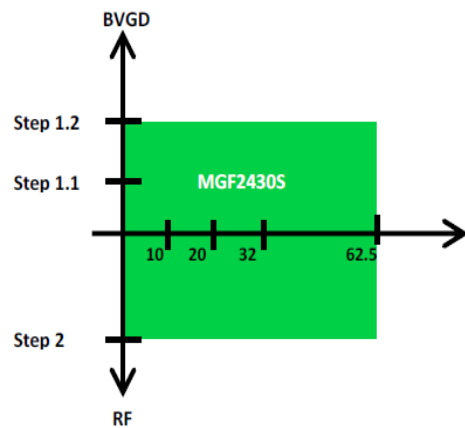
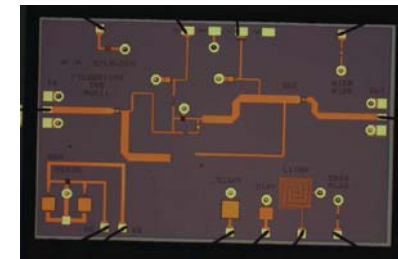
SUMITOMO HP  
FLL120MK



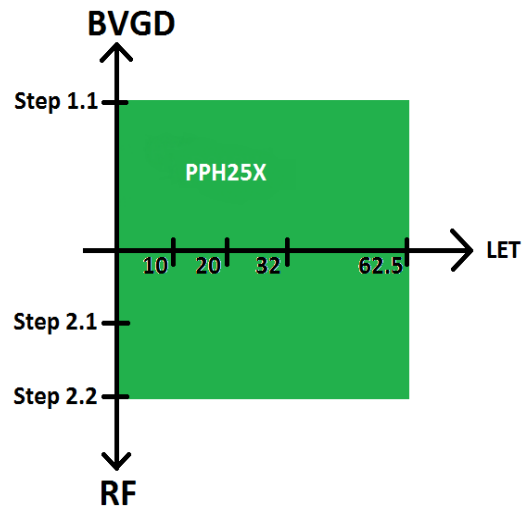
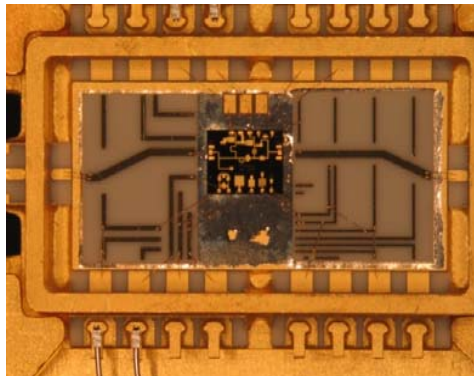
SUMITOMO LNA  
FHX35LR



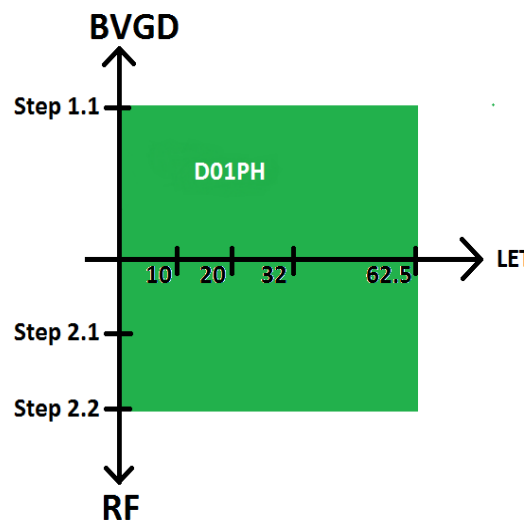
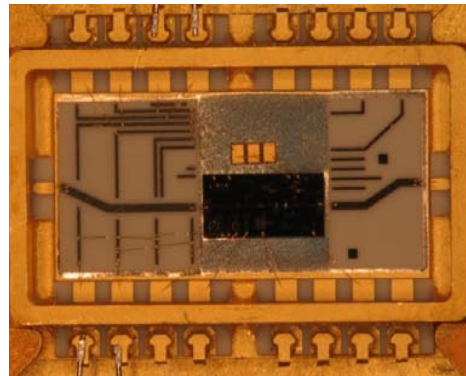
OMMIC ED02AH  
TCV



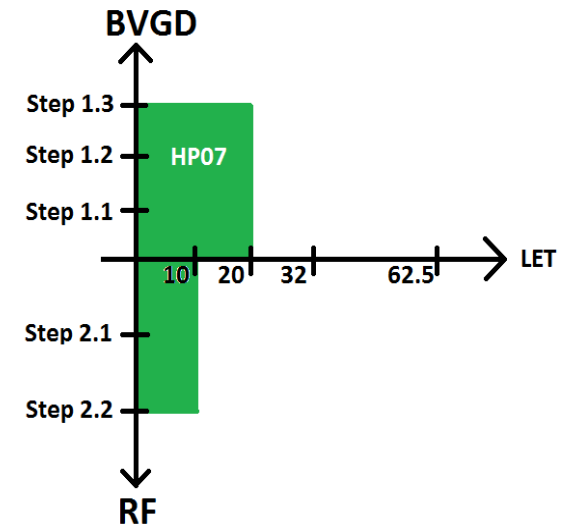
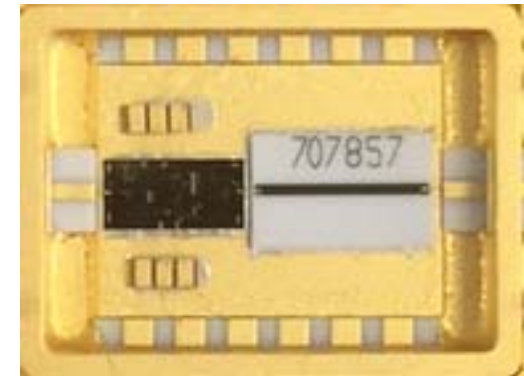
UMS PPH25X



OMMIC D01PH



UMS HP07





MITSUBISHI  
HP MGF2430S

SUMITOMO HP  
FLL120MK

SUMITOMO LNA  
FHX35LR

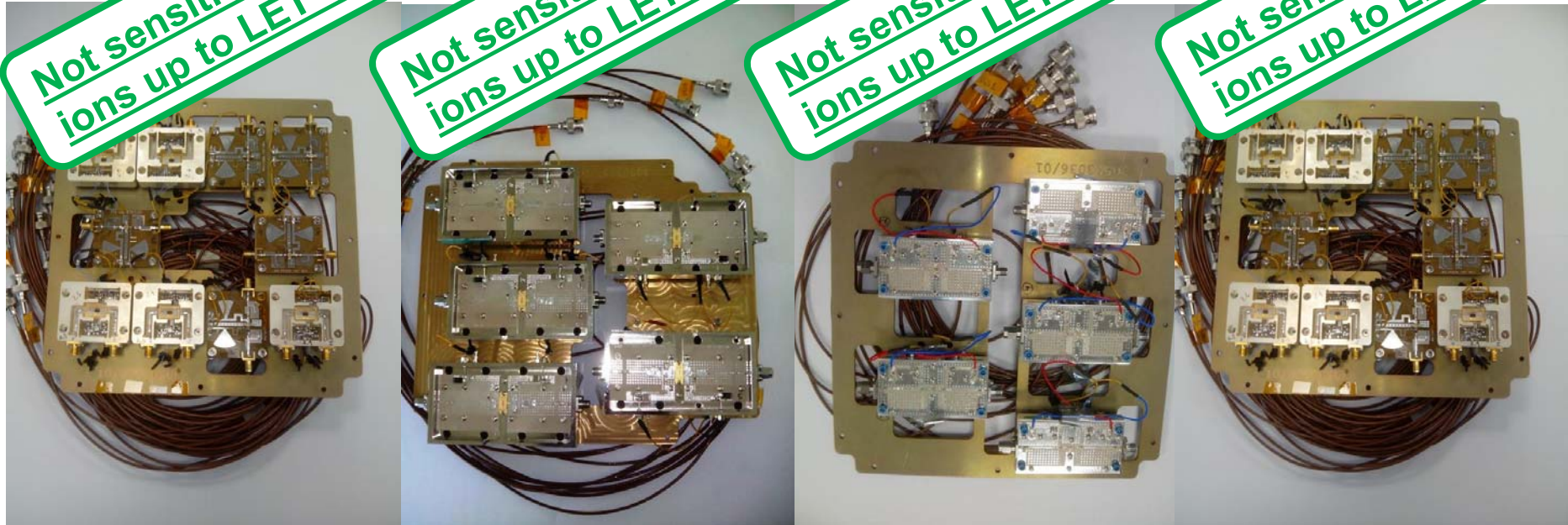
OMMIC ED02AH  
TCV

Not sensitive to heavy  
ions up to LET of 62.5

Not sensitive to heavy  
ions up to LET of 62.5

Not sensitive to heavy  
ions up to LET of 62.5

Not sensitive to heavy  
ions up to LET of 62.5



UMS PPH25X



OMMIC D01PH



UMS HP07





- ❑ Are radiation tests under DC sufficient ? and if RF, what RF signals?,
  - ✓ RF step stress test (increasing compression level) under heavy ions is recommended
- ❑ Do we need to test other technologies than power MESFET like HEMT, pHEMT?,
  - ✓ No sensitivity seen on pHEMT but cannot be extended to others without data
- ❑ Do we need to test per device, per lot, per function, per technology process ?
  - ✓ Consistency with previous data seems to show that testing per technology is satisfactory.
- ❑ What Test vehicle (TCV, DEC, MMIC) ?
  - ✓ TCV with DEC is OK